

REMARKS

Claims 1-18 are pending in this application.

Claims 1, 7, 9, 13, 14 and 18 have been amended. It is respectfully submitted that no new matter has been added.

REJECTIONS UNDER 35 U.S.C. § 103:

Claims 1-18 stand rejected under 35 U.S.C. 103(a) as being unpatentable over Pierrat (US 5,935,734) in view of Kawashima (US 6,991,896).

Amended claim 1 recites, *inter alia*, at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern, wherein the first longitudinal pitch is the distance from one center point between a pair of light shielding patterns to another center point between a neighboring pair of light shielding patterns in a longitudinal axis. Amended claims 9 and 14 recite, *inter alia*, a step of forming at least one through hole comprising locating the at least one through hole to evenly divide a first longitudinal pitch of the light-shielding pattern, wherein the first longitudinal pitch is the distance from one center point between a pair of light shielding patterns to another center point between a neighboring pair of light shielding patterns in a longitudinal axis.

Applicants respectfully submit that neither Pierrat, Kawashima, nor any combinations thereof discloses or suggests at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern, as essentially recited in amended claims 1, 9 and 14.

The Examiner acknowledges that Pierrat does not disclose at least one through hole having a size smaller than a distance between the light-shielding patterns. It follows that Pierrat does not disclose at least one through hole located to evenly divide a first

longitudinal pitch of the light-shielding pattern. For this element, the Examiner relies on Kawashima.

Applicants respectfully submit that Kawashima does not disclose or suggest at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern. Kawashima is directed to an exposure method including the step of providing a mask that arranges a contact-hole pattern. However, Kawashima is completely silent on a relative location of a contact hole with respect to a longitudinal pitch of the light-shielding pattern.

Accordingly, even assuming, *arguendo*, that Pierrat and Kawashima were combined, the combination does not disclose or suggest at least one through hole located to evenly divide a first longitudinal pitch of the light-shielding pattern.

Since claims 2-8, 10-13 and 15-18 depend from claims 1, 9 and 14, respectively, these dependent claims are also patentable for the same reasons given above for claims 1, 9 and 14.

Therefore, Applicants respectfully request that Examiner withdraw the rejection of claims 1-18 under 35 U.S.C. § 103(a) and that claims 1-18 are in condition for allowance.

An early and favorable reconsideration is earnestly solicited. If the Examiner has any further questions or comments, the Examiner may telephone Applicants' Attorney to reach a prompt disposition of this application.

Respectfully submitted,

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